

The thermostability of the Fe_{16}N_2 phase deposited on a GaAs substrate by ion-beam-assisted deposition

This article has been downloaded from IOPscience. Please scroll down to see the full text article.

1994 J. Phys.: Condens. Matter 6 L279

(<http://iopscience.iop.org/0953-8984/6/18/004>)

View [the table of contents for this issue](#), or go to the [journal homepage](#) for more

Download details:

IP Address: 171.66.16.147

The article was downloaded on 12/05/2010 at 18:17

Please note that [terms and conditions apply](#).

LETTER TO THE EDITOR

The thermostability of the Fe₁₆N₂ phase deposited on a GaAs substrate by ion-beam-assisted deposition

Hai Jiang, Kun Tao and Hengde Li

Department of Materials Science and Engineering, Tsinghua University, Beijing 100084, People's Republic of China

Received 17 March 1994

Abstract. An Fe–N film was deposited on a GaAs(100) substrate by ion-beam-assisted deposition at an N/Fe atomic arrival ratio of 0.12. The results from x-ray diffraction showed that the film consisted of the Fe₁₆N₂ phase. The results of an annealing experiment indicated that the Fe₁₆N₂ phase formed is stable after annealing at 150 °C. At 200 °C, the Fe₁₆N₂ started to decompose to α -Fe and γ' -Fe₄N, and it converted to α -Fe and γ' -Fe₄N completely at 300 °C. The magnetic properties of films annealed at different temperatures were also measured and the results are discussed.

Since the discovery of the giant magnetization of Fe₁₆N₂ by Kim and Takahashi [1], extensive research has been devoted to the investigation of the formation of the Fe₁₆N₂ phase and to the clarification of its magnetic properties. In recent work by the groups of Sugita and Nakajima [2–4], Fe–N films containing the Fe₁₆N₂ phase have been successfully formed by molecular beam epitaxy (MBE) and ion implantation. However, the Fe₁₆N₂ phase can only be formed at a thickness of several hundred ångströms by MBE. In the ion implantation process, the film thickness is also limited by the ion range. Therefore the amount of the Fe₁₆N₂ phase in the films prepared by the above methods is usually small. In this letter, we report the formation of an Fe–N film containing the Fe₁₆N₂ phase by ion-beam-assisted deposition and the thermostability of the Fe₁₆N₂ phase. The magnetic properties of the Fe–N film are also discussed. Other than the early work by Jack [5], the transformation of Fe₁₆N₂ by annealing has rarely been studied due to difficulties in the forming of Fe₁₆N₂, as is well known.

Experiments were performed in a high-vacuum system of ion-beam-assisted deposition. A base pressure of 8×10^{-5} Pa was achieved by using a cryogenic pump. A Kauffman ion source was used and its current density measured using a Faraday cup. The ion energy could vary from 2 to 30 keV. The partial pressure of N₂ gas (99.999%) was 5.0×10^{-3} Pa with the ion source operating. The evaporation of Fe (> 99.9%) was carried out using an electron gun. The deposition rate and film thickness were monitored using a thermal couple in contact with the back of the substrate. The N/Fe atomic arrival ratio at the substrate was obtained according to the evaporation rate and N-ion (N^+/N_2^+) current density during deposition. Table 1 lists the deposition conditions for the film. The annealing experiment was carried out in a vacuum system that had a base pressure of 1.1×10^{-4} Pa.

The structure of the films was analysed using x-ray diffraction (Cu K α radiation). The saturation magnetization was measured using a vibrating-sample magnetometer (VSM) applying an external field of 10 kOe parallel to the film plane. The Fe contents of the

Table 1. The preparation conditions of the film.

Base vacuum	$< 8 \times 10^{-5}$ Pa
N ₂ pressure	5×10^{-3} Pa
Ion energy	5 keV
Ion current density	35–60 $\mu\text{A cm}^{-2}$
Deposition rate	2–3 \AA s^{-1}
Film thickness	~ 3500 \AA

films were measured as follows. First the films were completely dissolved into 10% HCl solution, then inductively coupled plasma atomic emission spectrometry (ICP AES) was used to measure the Fe content in the solution. The error in the measurement of Fe content by this method was less than 3%.

According to Jack [5], the Fe₁₆N₂ (α'') structure is essentially a nitrogen martensite, in which the nitrogen atoms are completely ordered. Thus, in some cases, the Fe₁₆N₂ phase can be identified by the superlattice diffraction of Fe₁₆N₂, which does not appear in nitrogen martensite (α') with the same N concentration in which the N atoms are disordered. Figure 1 shows the XRD pattern of an Fe–N film deposited on a GaAs substrate at an N/Fe atomic arrival ratio of 0.12. It can be seen that a strong diffraction line appears at 58.8° (2θ), corresponding to a d -spacing of 1.57 \AA , which can be assigned as from Fe₁₆N₂(004) and α' (002). A weak line at about 28.5° (2θ) that only belongs to the superlattice diffraction line of Fe₁₆N₂(002) is also observed. Therefore, we can confirm that the Fe₁₆N₂ phase has been formed in the film. From the XRD pattern one can see that the intensity ratio $I(004)/I(002)$ is about 10, which is comparable to the theoretical value for Fe₁₆N₂. Thus, it can be considered that the peak at 58.8° (2θ) is mainly from the Fe₁₆N₂ phase, i.e. the Fe₁₆N₂ phase is predominant and the quantity of α' phase is small.

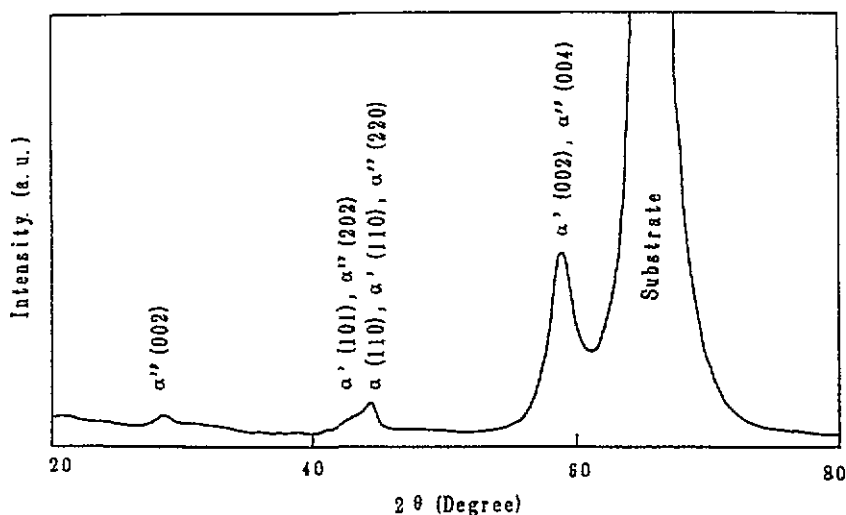


Figure 1. The XRD pattern of the Fe–N film: α , α -Fe; α' , N martensite; α'' , Fe₁₆N₂.

In order to investigate the thermostability of the Fe₁₆N₂ phase, the sample was divided into several plates, which were annealed in vacuum from 150 °C to 500 °C. For the film

annealed at 150 °C, no new line was found in the XRD pattern compared with that for the film before annealing, and the intensities of the Fe_{16}N_2 lines were also not increased, which indicates that the film is stable at 150 °C and a short annealing time at low temperature has little influence on the crystallites of Fe_{16}N_2 . However, for a higher annealing temperature, it is observed that the phases in the films have changed. Figure 2 shows the XRD patterns of the films annealed from 200 °C to 500 °C. From figure 2(a) we can see that diffraction lines from γ' - Fe_4N appear in the pattern. According to the studies by Jack [5], the Fe_{16}N_2 is an intermediate phase, which first forms from N martensite and gradually decomposes to α -Fe and γ' - Fe_4N . Thus, it can be assumed that Fe_{16}N_2 has started to decompose to α -Fe and γ' - Fe_4N at 200 °C, but most of the Fe_{16}N_2 still remains in the film after annealing for 2 h. With further increase of annealing temperature, more Fe_{16}N_2 phase will transform to α -Fe and γ' - Fe_4N . From figure 2(c) we can see that the Fe_{16}N_2 phase has converted to α -Fe and γ' - Fe_4N completely after annealing at 300 °C. The XRD pattern of the film after annealing at 400 °C shows sharper γ' - Fe_4N lines, which indicates larger crystallites of γ' - Fe_4N . When the temperature reaches 500 °C, since the film has reacted with the GaAs substrate, many lines are observed in addition to the one for α -Fe and γ' - Fe_4N .

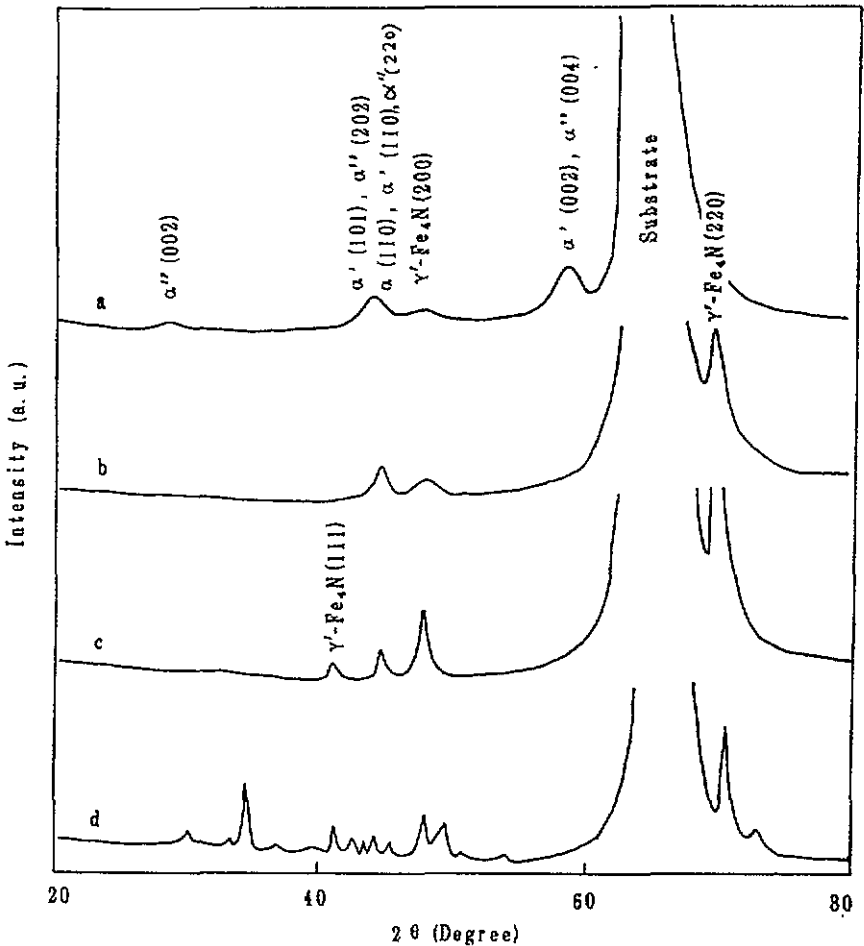


Figure 2. XRD patterns of the films after annealing at different temperatures.

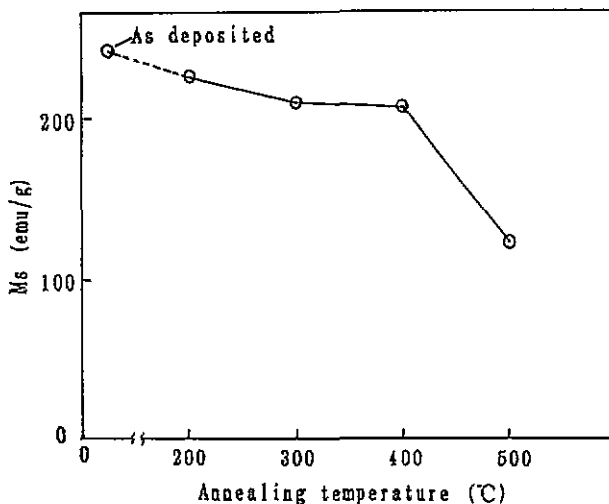


Figure 3. The dependence of the saturation magnetization (M_s) of the films on the annealing temperature.

The change of the phase composition causes the change in magnetic properties of the films. Figure 3 shows the variation of saturation magnetization (M_s) with annealing temperature. It can be seen that the M_s of the film before annealing is 237 emu g^{-1} , which is significantly larger than that of bulk Fe (210 emu g^{-1}). Since it is difficult to calculate exactly the fraction of the Fe_{16}N_2 phase in the film from its XRD pattern, the M_s -value of the Fe_{16}N_2 cannot be established. However, a rough estimation from XRD intensities indicates that the fraction of Fe_{16}N_2 phase in the film is over 55 vol%; the M_s -value of the Fe_{16}N_2 formed in our experiment seems less than that reported by Kim and Takahashi [1].

M_s -values of the films after annealing at 300°C and 400°C are about 200 emu g^{-1} ; this value is between the M_s -values of $\alpha\text{-Fe}$ and $\gamma'\text{-Fe}_4\text{N}$ since the films consist of these two phases. For the film annealed at 500°C , the M_s -value of the film decreases and drops to 120 emu g^{-1} due to the occurrence of a reaction between the GaAs substrate and the film.

In summary, it is possible to form an Fe-N film containing the Fe_{16}N_2 phase by ion-beam-assisted deposition. The Fe_{16}N_2 was stable at 150°C and started to transform into $\alpha\text{-Fe}$ and $\gamma'\text{-Fe}_4\text{N}$ at 200°C . After annealing at 300°C for 2 h the Fe_{16}N_2 converted completely to $\alpha\text{-Fe}$ and $\gamma'\text{-Fe}_4\text{N}$. Although the M_s -value of the Fe-N film containing Fe_{16}N_2 is significantly higher than that of $\alpha\text{-Fe}$, the M_s of Fe_{16}N_2 seems less than that reported. An accurate measurement of Fe_{16}N_2 in the film is necessary to determine its M_s -value. This part of the work is in progress.

References

- [1] Kim T K and Takahashi M 1972 *Appl. Phys. Lett.* **20** 492
- [2] Komuto M, Kozono Y, Hanazono M and Sugita Y 1990 *J. Appl. Phys.* **67** 5126
- [3] Nakajima K and Okamoto S 1989 *Appl. Phys. Lett.* **54** 2536
- [4] Nakajima K and Okamoto S 1990 *Appl. Phys. Lett.* **56** 92
- [5] Jack K H 1951 *Proc. R. Soc. A* **208** 216